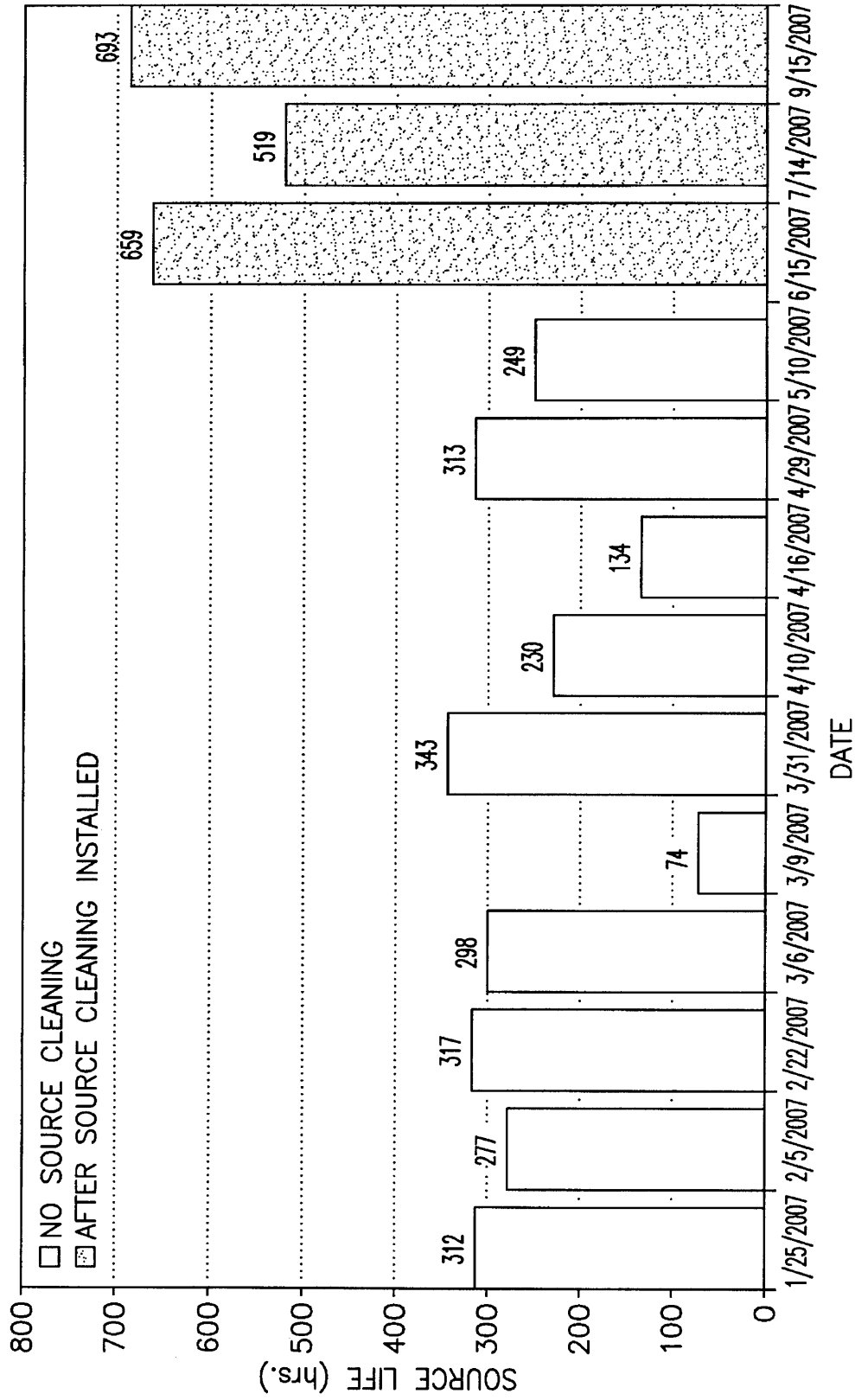
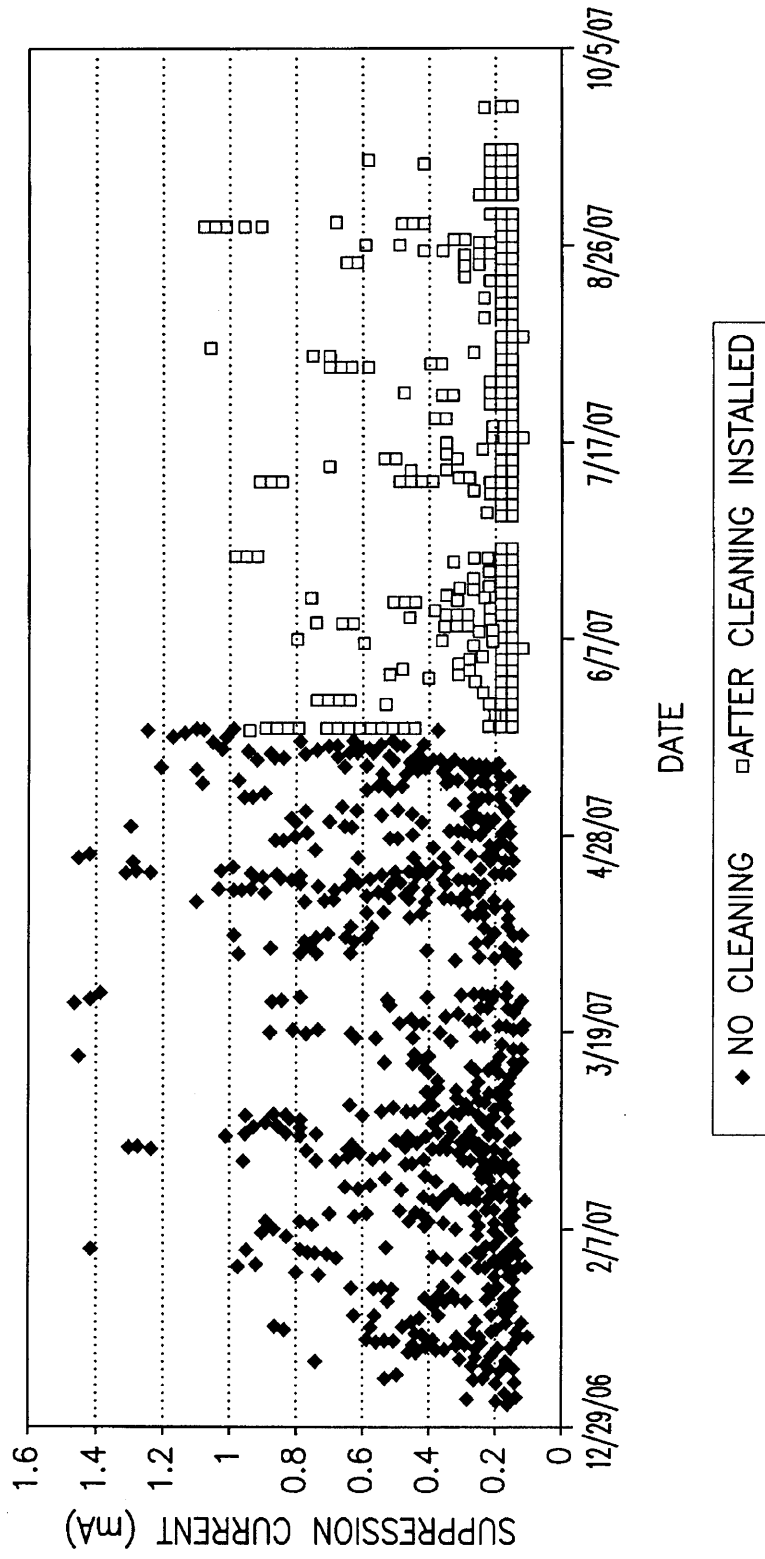




EFFECT OF In-Situ CLEANING ON ION SOURCE LIFE

FIG.1



AVERAGE SUPPRESSION LEAKAGE CURRENT BY WAFER LOT

FIG.2

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FIG.3A



FIG.3B

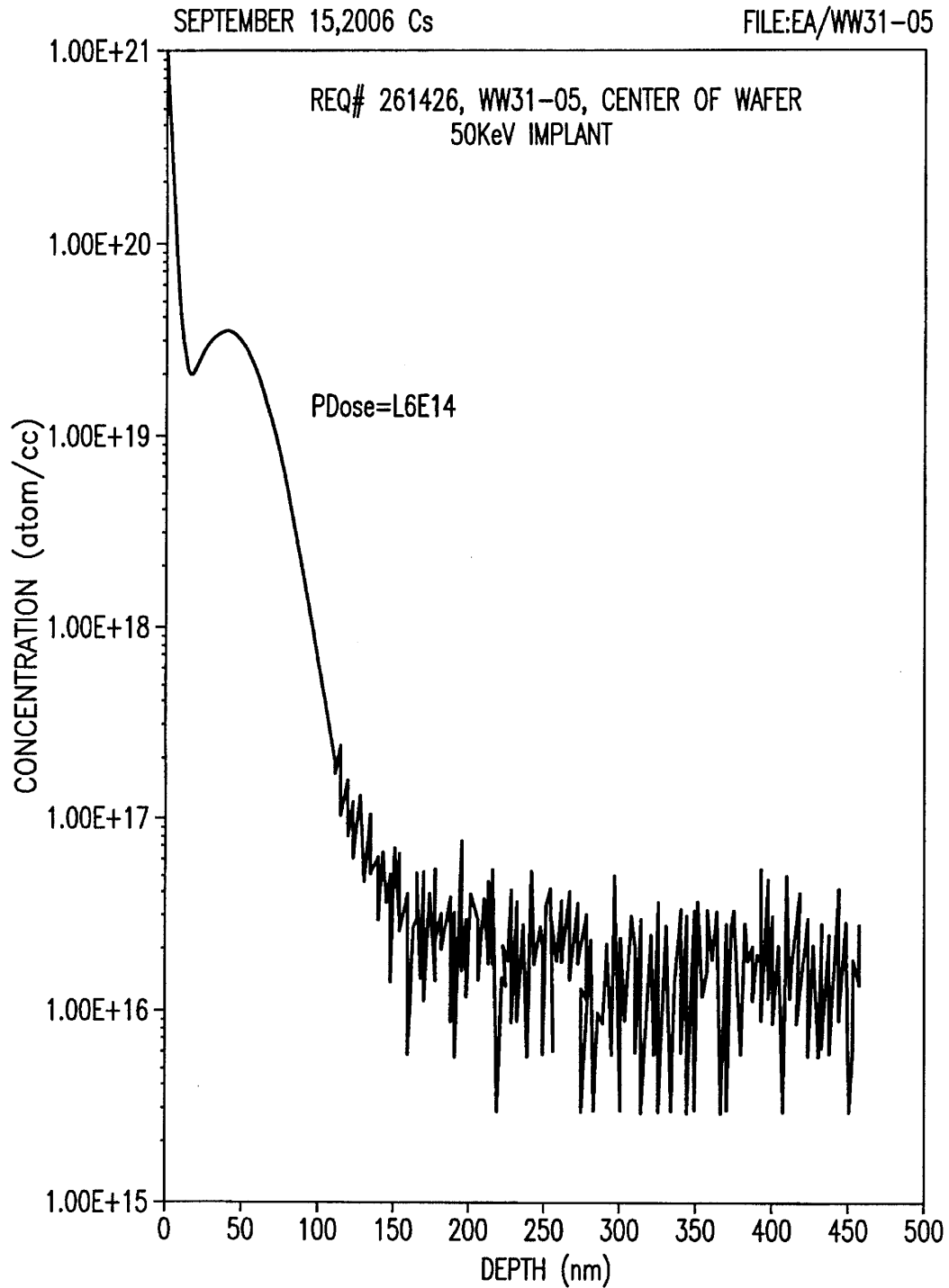


FIG.4A

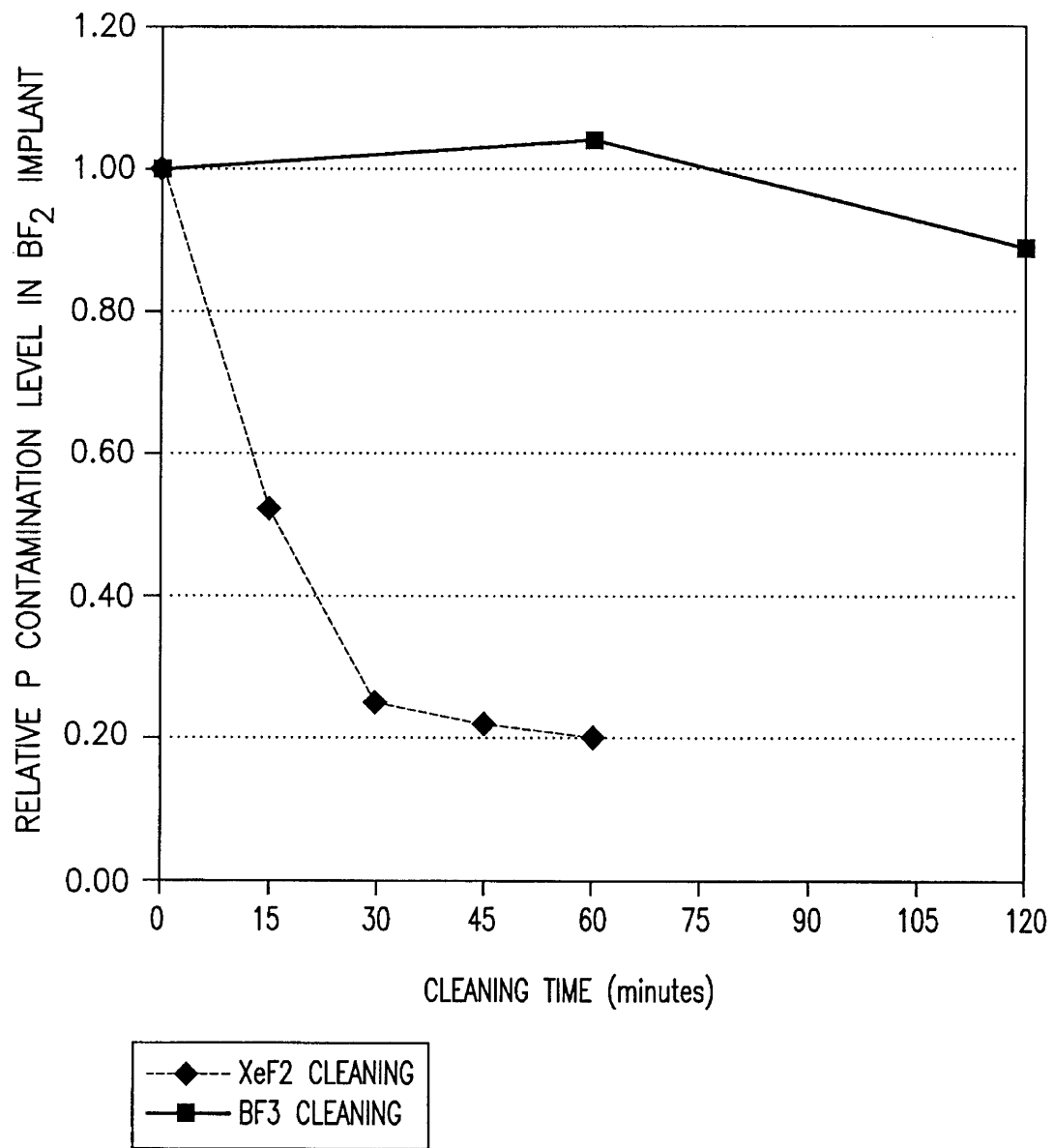


FIG.4B

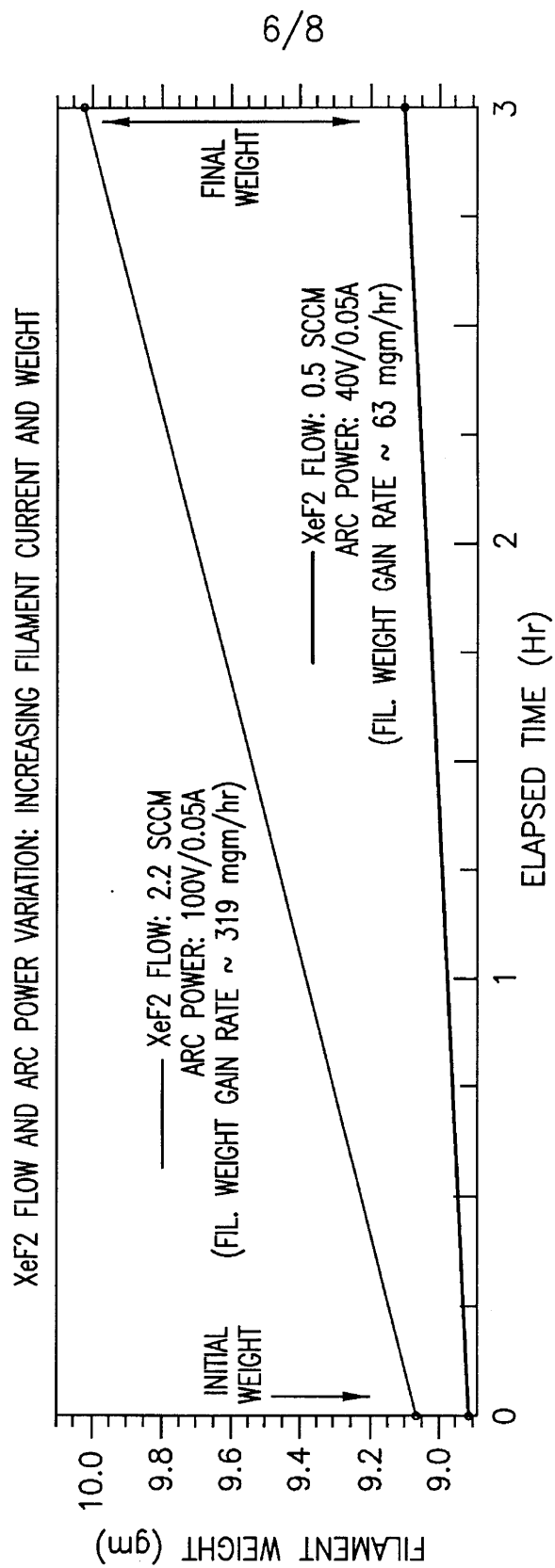


FIG.5A

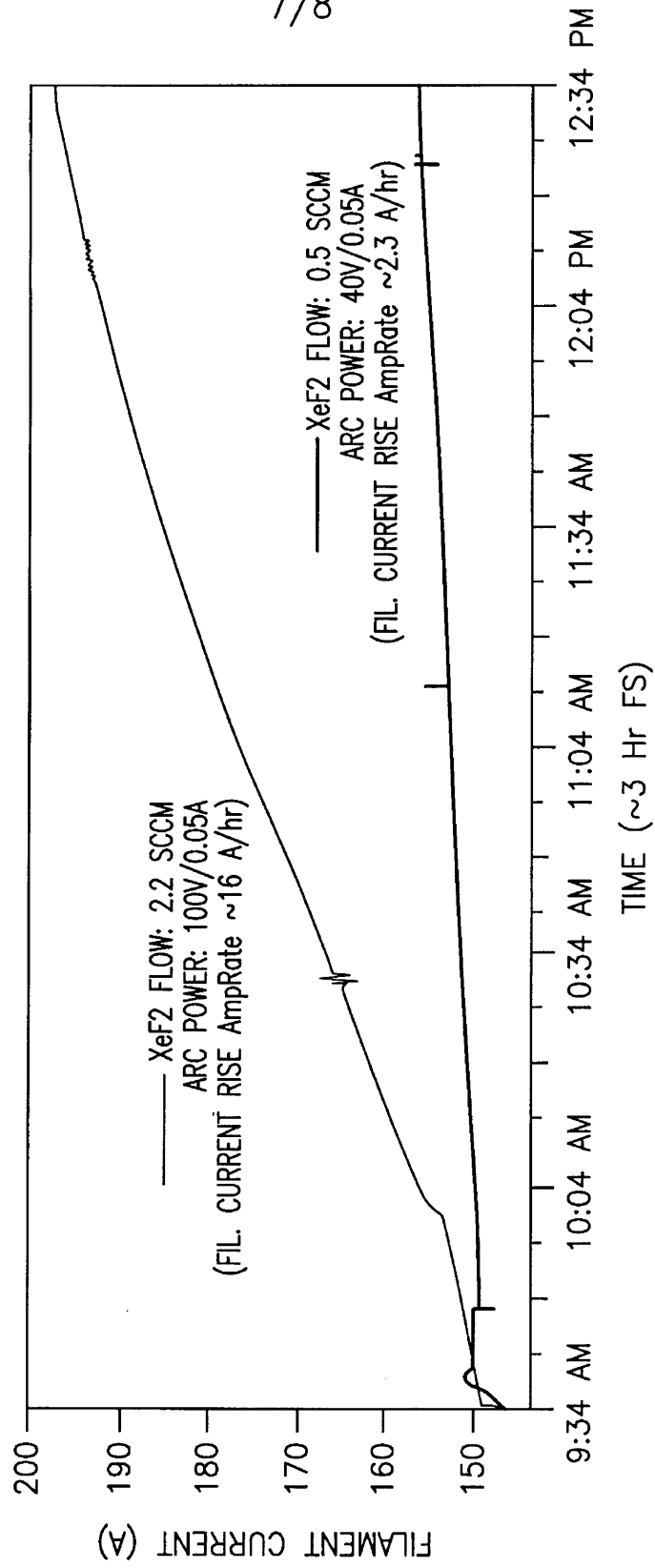


FIG.5B

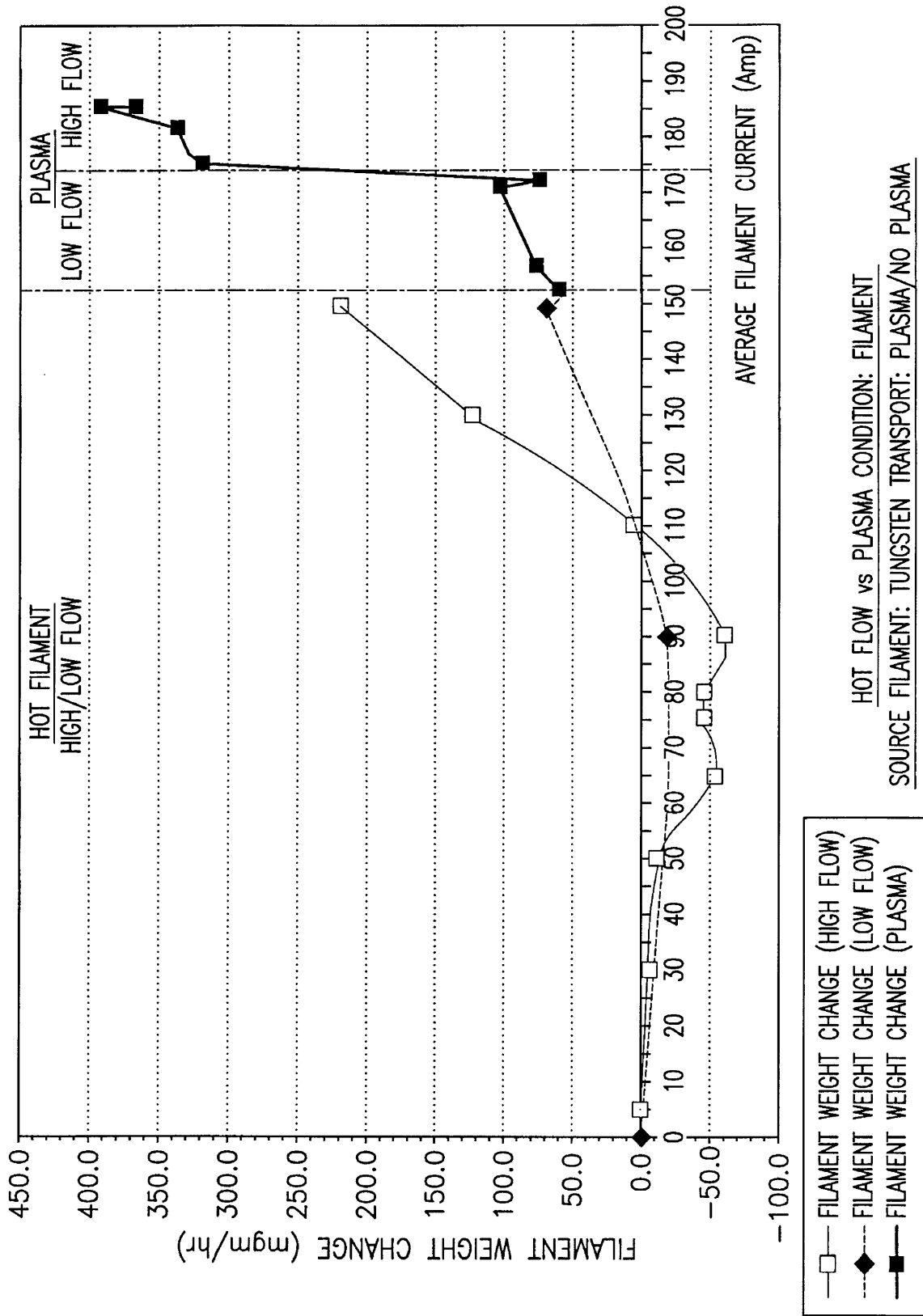


FIG.6